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**INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION**

(PTO-1449)



ATTY. DOCKET NO.
004393 USA
C/01/MTCG/PCTRL

SERIAL NO.
10/686,589

APPLICANT
Sasson R. SOMEKH et al.



FILING DATE
October 17, 2003

GROUP
2121


U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
EF	4,901,218	02/13/90	Cornwell			03/04/88
	5,427,878	06/27/95	Corliss			05/16/94
	5,761,065	06/02/98	Kittler et al.			03/30/95
	5,862,054	01/19/99	Li			02/20/97
	5,912,678	06/15/99	Saxena et al.			04/14/97
	5,926,690	07/20/99	Toprac et al.			05/28/97
	6,074,443	06/13/00	Venkatesh et al.			01/29/98
	6,111,634	08/29/00	Pecen et al.			05/28/97
	6,150,664	11/21/00	Su			06/29/99
	6,245,581 B1	06/12/01	Bonser et al.			04/19/00
	2001/0044667 A1	11/22/01	Nakano et al.			05/16/01
	6,346,426 B1	02/12/02	Toprac et al.			11/17/00
	6,363,294 B1	03/26/02	Coronel et al.			12/29/98
	6,442,496 B1	08/27/02	Pasadyn et al.			08/08/00
	6,486,492 B1	11/26/02	Su			11/20/00
	6,492,281 B1	12/10/02	Song et al.			09/22/00
	6,540,591 B1	04/01/03	Pasadyn et al.			04/18/01
	6,560,504 B1	05/06/03	Goodwin et al.			09/29/99
	6,590,179 B2	07/08/03	Tanaka et al.			02/26/01
	6,604,012 B1	08/05/03	Cho et al.			08/23/00
	6,618,692 B2	09/09/03	Takahashi et al.			02/26/01
	6,625,497 B2	09/23/03	Fairbairn et al.			07/10/01
EF	6,640,151 B1	10/28/03	Somekh et al.			12/22/99
EXAMINER			DATE CONSIDERED			
			6/17/04			

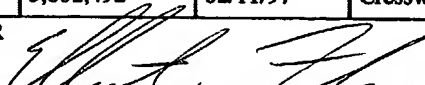
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				APPLICANT Sasson R. SOMEKH et al.			
				FILING DATE October 17, 2003		GROUP 2121	
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
EF	0 397 924 A1	11/22/90	Europe			X	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
EF	Rocha, Joao and Carlos Ramos. September 12, 1994. "Task Planning for Flexible and Agile Manufacturing Systems." <i>Intelligent Robots and Systems '94. Advanced Robotic Systems and the Real World, IROS '94. Proceedings of the IEEE/RSJ/GI International Conference on Munich, Germany 12-16 Sept. 1994.</i> New York, New York: IEEE. pp. 105-112.						
	March 15, 2002. Office Action for U.S. Serial No. 09/469,227, filed December 22, 1999.						
	March 29, 2002. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.						
	June 20, 2002. Office Action for U.S. Serial No. 09/619,044, filed July 19, 2000.						
	September 26, 2002. Office Action for U.S. Serial No. 09/637,620, filed August 11, 2000.						
	October 23, 2002. Office Action for U.S. Serial No. 09/469,227, filed December 22, 1999.						
	December 17, 2002. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.						
	February 10, 2003. Office Action for U.S. Serial No. 09/619,044, filed July 19, 2000.						
	April 9, 2003. Office Action for U.S. Serial No. 09/928,474, filed August 14, 2001.						
	May 8, 2003. Office Action for U.S. Serial No. 09/637,620, filed August 11, 2000.						
	June 18, 2003. Office Action for U.S. Serial No. 09/655,542, filed September 6, 2000.						
	August 8, 2003. International Search Report for PCT/US03/08513.						
	August 25, 2003. Office Action for U.S. Serial No. 10/100,184, filed March 19, 2002.						
	September 15, 2003. Office Action for U.S. Serial No. 09/928,474, filed August 14, 2001.						
	November 5, 2003. Office Action for U.S. Serial No. 10/172,977, filed June 18, 2002.						
	December 1, 2003. Office Action for U.S. Serial No. 10/173,108, filed June 18, 2002.						
	December 11, 2003. Office Action for U.S. Serial No. 09/943,383, filed August 31, 2001.						
	December 16, 2003. International Search Report for PCT/US03/23964.						
	January 20, 2004. Office Action for U.S. Serial No. 09/927,444, filed August 13, 2001.						
	January 23, 2004. International Search Report for PCT/US02/24860.						
EF	February 2, 2004. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.						
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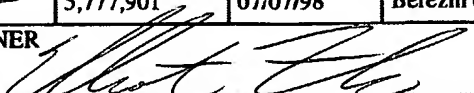
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U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
ELF	3,205,485	09/07/65	Noltingk			10/21/60	
	3,229,198	01/11/66	Libby			09/28/62	
	3,767,900	10/23/73	Chao et al.			06/23/71	
	3,920,965	11/18/75	Sohrwardy			03/04/74	
	4,000,458	12/28/76	Miller et al.			08/21/75	
	4,302,721	11/24/81	Urbanek et al.			05/15/79	
	4,368,510	01/11/83	Anderson			10/20/80	
	4,616,308	10/07/86	Morshedi et al.			12/02/85	
	4,663,703	05/05/87	Axelby et al.			10/02/85	
	4,698,766	10/06/87	Entwistle et al.			05/17/85	
	4,750,141	06/07/88	Judell et al.			11/26/85	
	4,757,259	07/12/88	Charpentier			11/05/86	
	4,796,194	01/03/89	Atherton			08/20/86	
	4,938,600	07/03/90	Into			02/09/89	
	4,967,381	10/30/90	Lane et al.			07/06/89	
	5,089,970	02/18/92	Lee et al.			10/05/89	
	5,108,570	04/28/92	Wang			03/30/90	
	5,208,765	05/04/93	Turnbull			07/20/90	
	5,220,517	06/15/93	Sierk et al.			08/31/90	
	5,226,118	07/06/93	Baker et al.			01/29/91	
	5,231,585	07/27/93	Kobayashi et al.			06/20/90	
	5,236,868	08/17/93	Nulman			04/20/90	
	5,260,868	11/09/93	Gupta et al.			10/15/91	
	5,270,222	12/14/93	Moslehi			12/31/90	
	5,283,141	02/01/94	Yoon et al.			03/05/92	
	5,295,242	03/15/94	Mashruwala et al.			11/02/90	
ELF	5,309,221	05/03/94	Fischer et al.			12/31/91	
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9/F	5,329,463	07/12/94	Sierk et al.			01/13/93
	5,338,630	08/16/94	Yoon et al.			11/18/93
	5,347,446	09/13/94	Iino et al.			02/10/92
	5,367,624	11/22/94	Cooper			06/11/93
	5,375,064	12/20/94	Bollinger			12/02/93
	5,398,336	03/14/95	Tantry et al.			06/16/93
	5,402,367	03/28/95	Sullivan et al.			07/19/93
	5,408,405	04/18/95	Mozumder et al.			09/20/93
	5,410,473	04/25/95	Kaneko et al.			12/16/92
	5,420,796	05/30/95	Weling et al.			12/23/93
	5,469,361	11/21/95	Moyne			06/06/94
	5,485,082	01/16/96	Wisspeintner et al.			04/05/90
	5,490,097	02/06/96	Swenson et al.			08/06/93
	5,495,417	02/27/96	Fuduka et al.			03/16/93
	5,497,316	03/05/96	Sierk et al.			04/04/95
	5,497,381	03/05/96	O'Donoghue et al.			06/01/95
	5,503,707	04/02/96	Maung et al.			09/22/93
	5,508,947	04/16/96	Sierk et al.			05/13/94
	5,511,005	04/23/96	Abbe et al.			02/16/94
	5,519,605	05/21/96	Cawfield			10/24/94
	5,525,808	06/11/96	Irie et al.			12/20/94
	5,526,293	06/11/96	Mozumder et al.			12/17/93
	5,541,510	06/30/96	Danielson			04/06/95
	5,546,312	08/13/96	Mozumder et al.			02/24/94
	5,553,195	09/03/96	Meijer			09/29/94
	5,586,039	12/17/96	Hirsch et al.			02/27/95
	5,599,423	02/04/97	Parker et al.			06/30/95
9/F	5,602,492	02/11/97	Cresswell et al.			04/28/94
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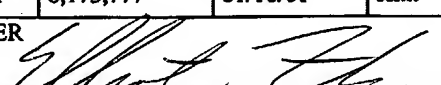
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	5,617,023	04/01/97	Skalski			02/02/95
	5,627,083	05/06/97	Tounai			05/12/95
	5,629,216	05/13/97	Wijaranakula et al.			02/27/96
	5,642,296	06/24/97	Saxena			07/29/93
	5,646,870	07/08/97	Krivokapic et al.			02/13/95
	5,649,169	07/15/97	Berezin et al.			06/20/95
	5,654,903	08/05/97	Reitman et al.			11/07/95
	5,655,951	08/12/97	Meikle et al.			09/29/95
	5,657,254	08/12/97	Sierk et al.			04/15/96
	5,661,669	08/26/97	Mozumder et al.			06/07/95
	5,663,797	09/02/97	Sandhu			05/16/96
	5,664,987	09/09/97	Renteln			09/04/96
	5,665,199	09/09/97	Sahota et al.			06/23/95
	5,666,297	09/09/97	Britt et al.			05/13/94
	5,667,424	09/16/97	Pan			09/25/96
	5,674,787	10/07/97	Zhao et al.			01/16/96
	5,694,325	12/02/97	Fukuda et al.			11/22/95
	5,698,989	12/16/97	Nulman			09/13/96
	5,719,495	02/17/98	Moslehi			06/05/96
	5,719,796	02/17/98	Chen			12/04/95
	5,735,055	04/07/98	Hochbein et al.			04/23/96
	5,740,429	04/14/98	Wang et al.			07/07/95
	5,751,582	05/12/98	Saxena et al.			09/24/96
	5,754,297	05/19/98	Nulman			04/14/97
	5,761,064	06/02/98	La et al.			10/06/95
	5,764,543	06/09/98	Kennedy			06/16/95
EF	5,777,901	07/07/98	Berezin et al.			09/29/95
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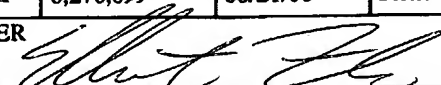
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SIF	5,787,021	07/28/98	Samaha			12/18/95	
	5,787,269	07/28/98	Hyodo			09/19/95	
	5,808,303	09/15/98	Schlagheck et al.			01/29/97	
	5,812,407	09/22/98	Sato et al.			08/12/97	
	5,823,854	10/20/98	Chen			05/28/96	
	5,825,913	10/20/98	Rostami et al.			07/18/95	
	5,828,778	10/27/98	Hagi et al.			06/12/96	
	5,832,224	11/03/98	Fehskens et al.			06/14/96	
	5,838,595	11/17/98	Sullivan et al.			11/25/96	
	5,844,554	12/01/98	Geller et al.			09/17/96	
	5,857,258	01/12/99	Penzes et al.			05/12/94	
	5,859,964	01/12/99	Wang et al.			10/25/96	
	5,859,975	01/12/99	Brewer et al.			08/09/96	
	5,863,807	01/26/99	Jang et al.			03/15/96	
	5,870,306	02/09/99	Harada			06/13/97	
	5,883,437	03/16/99	Maruyama et al.			12/28/95	
	5,889,991	03/30/99	Consolatti et al.			12/06/96	
	5,903,455	05/11/99	Sharpe, Jr. et al.			12/12/96	
	5,910,011	06/08/99	Cruse			05/12/97	
	5,910,846	06/08/99	Sandhu			08/19/97	
5,916,016	06/29/99	Bothra			10/23/97		
5,923,553	07/13/99	Yi			10/05/96		
5,930,138	07/27/99	Lin et al.			09/10/97		
5,940,300	08/17/99	Ozaki			05/08/97		
5,943,237	08/24/99	Van Boxem			10/17/97		
5,960,185	09/28/99	Nguyen			06/24/96		
5,960,214	09/28/99	Sharpe, Jr. et al.			12/04/96		
WF	5,961,369	10/05/99	Bartels et al.			06/04/98	
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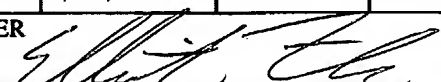
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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
<i>ELF</i>	5,963,881	10/05/99	Kahn et al.			10/20/97	
	5,978,751	11/02/99	Pence et al.			02/25/97	
	5,982,920	11/09/99	Tobin, Jr. et al.			01/08/97	
	6,017,771	01/25/00	Yang et al.			04/27/98	
	6,036,349	03/14/00	Gombar			07/26/96	
	6,041,270	03/21/00	Steffan et al.			12/05/97	
	6,054,379	04/25/00	Yau et al.			02/11/98	
	6,064,759	05/16/00	Buckley et al.			11/06/97	
	6,072,313	06/06/00	Li et al.			06/17/97	
	6,078,845	06/20/00	Friedman			11/25/96	
	6,097,887	08/01/00	Hardikar et al.			10/27/97	
	6,108,092	08/22/00	Sandhu			06/08/99	
	6,112,130	08/29/00	Fukuda et al.			10/01/97	
	6,127,263	10/03/00	Parikh			07/10/98	
	6,128,016	10/03/00	Coelho et al.			12/20/96	
	6,136,163	10/24/00	Cheung et al.			03/05/99	
	6,141,660	10/31/00	Bach et al.			07/16/98	
	6,143,646	11/07/00	Wetzel			06/03/97	
	6,148,099	11/14/00	Lee et al.			07/03/97	
	6,148,239	11/14/00	Funk et al.			12/12/97	
	6,148,246	11/14/00	Kawazome			06/10/98	
	6,159,075	12/12/00	Zhang			10/13/99	
	6,159,644	12/12/00	Satoh et al.			03/06/96	
	6,161,054	12/12/00	Rosenthal et al.			09/17/98	
	6,169,931	01/02/01	Runnels			06/29/98	
	6,172,756	01/09/01	Chalmers et al.			12/11/98	
6,173,240	01/09/01	Sepulveda et al.			11/02/98		
<i>ELF</i>	6,175,777	01/16/01	Kim			01/16/98	
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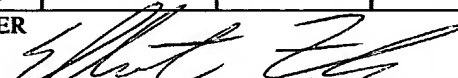
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EF	6,178,390	01/23/01	Jun			09/08/98	
	6,183,345	02/06/01	Kamono et al.			03/20/98	
	6,185,324	02/06/01	Ishihara et al.			01/31/95	
	6,191,864	02/20/01	Sandhu			02/29/00	
	6,192,291	02/20/01	Kwon			10/08/98	
	6,197,604	03/06/01	Miller et al.			10/01/98	
	6,204,165	03/20/01	Ghoshal			06/24/99	
	6,210,983	04/03/01	Atchison et al.			06/15/99	
	6,211,094	04/03/01	Jun et al.			08/23/99	
	6,214,734	04/10/01	Bothra et al.			11/20/98	
	6,217,412	04/17/01	Campbell et al.			08/11/99	
	6,219,711	04/17/01	Chari			10/01/97	
	6,222,936	04/24/01	Phan et al.			09/13/99	
	6,226,792	05/01/01	Goiffon et al.			10/14/98	
	6,230,069	05/08/01	Campbell et al.			06/26/98	
	6,236,903	05/22/01	Kim et al.			09/25/98	
	2001/0001755	05/24/01	Sandhu et al.			12/29/00	
	6,240,330	05/29/01	Kurtzberg et al.			05/28/97	
	6,240,331	05/29/01	Yun			08/18/98	
	2001/0003084	06/07/01	Finarov			12/04/00	
	6,246,972	06/12/01	Klimasauskas			05/27/99	
	6,248,602	06/19/01	Bode et al.			11/01/99	
	6,249,712	06/19/01	Boiquaye			09/25/96	
	6,252,412	06/26/01	Talbot et al.			01/08/99	
	6,253,366	06/26/01	Mutschler, III			03/31/99	
	6,263,255	07/17/01	Tan et al.			05/18/98	
	6,276,989	08/21/01	Campbell et al.			08/11/99	
EF	6,278,899	08/21/01	Piche et al.			10/06/98	
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GLF	6,280,289	08/28/01	Wiswesser et al.			11/02/98	
	6,284,622	09/04/01	Campbell et al.			10/25/99	
	6,287,879	09/11/01	Gonzales et al.			08/11/99	
	6,290,572	09/18/01	Hofmann			03/23/00	
	6,292,708	09/18/01	Allen et al.			06/11/98	
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	6,304,999	10/16/01	Toprac et al.			10/23/00	
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	6,320,655	11/20/01	Matsushita et al.			03/15/00	
	2001/0042690	11/22/01	Talieh			12/14/00	
	6,324,481	11/27/01	Atchison et al.			06/15/99	
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	6,379,980	04/30/02	Toprac			07/26/00	
	6,388,253	05/14/02	Su			11/02/00	
GLF	6,389,491	05/14/02	Jacobson et al.			03/23/99	
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SG	2002/0058460	05/16/02	Lee et al.			09/14/01	
	6,395,152	05/28/02	Wang			07/02/99	
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	2002/0081951	06/27/02	Boyd et al.			02/20/02	
	2002/0089676	07/11/02	Pecen et al.			04/26/00	
	2002/0102853	08/01/02	Li et al.			12/20/01	
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	2002/0113039	08/22/02	Mok et al.			02/16/01	
	6,440,295	08/27/02	Wang			02/04/00	
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	6,479,990	11/12/02	Mednikov et al.			06/18/01	
	2002/0185658	12/12/02	Inoue et al.			06/14/01	
	2002/0193902	12/19/02	Shanmugasundram et al.			06/18/02	
	2002/0197745	12/26/02	Shanmugasundram et al.			08/31/01	
	2002/0197934	12/26/02	Paik			11/30/01	
	2002/0199082	12/26/02	Shanmugasundram et al.			06/18/02	
	6,503,839	01/07/03	Gonzales et al.			07/03/01	
	2003/0020909	01/30/03	Adams et al.			04/09/01	
	2003/0020928	01/30/03	Ritzdorf et al.			07/09/01	
	6,517,413	02/11/03	Hu et al.			10/25/00	
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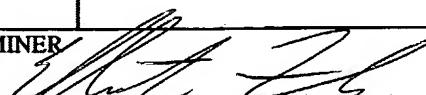
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ELF	09/363,966	07/29/99	Arackaparambil et al.	Computer Integrated Manufacturing Techniques			
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ELF	61-66104	04/04/86	Japan			X	
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	2,165,847	08/29/91	Canada			X	
	2,194,855	08/29/91	Canada			X	
	3-202710	09/04/91	Japan			X	
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	06-110894	04/22/94	Japan			X	
	06-176994	06/24/94	Japan			X	
	06-184434	07/05/94	Japan			X	
	06-252236	09/09/94	Japan			X	
	06-260380	09/16/94	Japan			X	
	EP 0 621 522 A2	10/26/94	Europe			X	
	WO 95/34866	12/21/95	WO			X	
	8-23166	01/23/96	Japan			X	
	08-50161	02/20/96	Japan			X	
	08-149583	06/07/96	Japan			X	
	08-304023	11/22/96	Japan			X	
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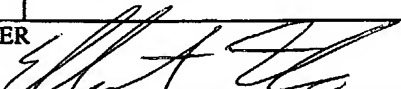
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	10-34522	02/10/98	Japan			X	
	10-173029	06/26/98	Japan			X	
	EP 0 869 652	10/07/98	Europe			X	
	WO 98/45090	10/15/98	WO			X	
	EP 0 877 308 A2	11/11/98	Europe			X	
	EP 0 881 040 A2	12/02/98	Europe			X	
	EP 0 895 145 A1	02/03/99	Europe			X	
	WO 99/09371	02/25/99	WO			X	
	11-67853	03/09/99	Japan			X	
	EP 0 910 123	04/21/99	Europe			X	
	11-126816	05/11/99	Japan			X	
	11-135601	05/21/99	Japan			X	
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	WO 00/05759	02/03/00	WO			X	
	WO 00/35063	06/15/00	WO			X	
	2000-183001	06/30/00	Japan			X	
	WO 00/54325	09/14/00	WO			X	
	GB 2 347 885 A	09/20/00	United Kingdom			X	
	WO 00/79355 A1	12/28/00	WO			X	
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	EP 1 067 757 A1	01/10/01	Europe			X	
	EP 1 071 128 A2	01/24/01	Europe			X	
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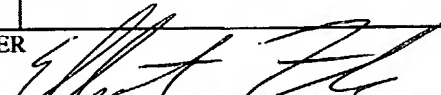
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EF	2001-76982	03/23/01	Japan			X	
	WO 01/25865	04/12/01	WO			X	
	EP 1 092 505 A2	04/18/01	Europe			X	
	WO 01/33277	05/10/01	WO			X	
	WO 01/33501 A1	05/10/01	WO			X	
	434103	05/16/01	Taiwan			X	
	436383	05/28/01	Taiwan			X	
	WO 01/52055 A3	07/19/01	WO			X	
	WO 01/57823 A2	08/09/01	WO			X	
	455938	09/21/01	Taiwan			X	
	455976	09/21/01	Taiwan			X	
	2001-284299	10/12/01	Japan			X	
	2001-305108	10/31/01	Japan			X	
	EP 1 072 967 A3	11/21/01	Europe			X	
	2002-9030	01/11/02	Japan			X	
	EP 1 182 526 A2	02/27/02	Europe			X	
	WO 02/17150 A1	02/28/02	WO			X	
	WO 02/33737 A2	04/25/02	WO			X	
	WO 02/074491	09/26/02	WO			X	
	2002-343754	11/29/02	Japan			X	
	WO 02/31613 A2	04/18/02	WO			X	
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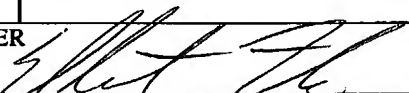
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EF	Ostanin, Yu.Ya. October 1981. "Optimization of Thickness Inspection of Electrically Conductive Single-Layer Coatings with Laid-on Eddy-Current Transducers (Abstract)." <i>Defektoskopiya</i> , vol. 17, no. 10, pp. 45-52. Moscow, USSR.		
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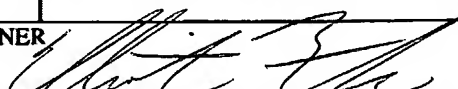
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EF	Matsuyama, Akira and Jessi Niou. 1993. "A State-of-the-Art Automation System of an ASIC Wafer Fab in Japan." <i>IEEE/SEMI International Semiconductor Manufacturing Science Symposium</i> , pp. 42-47.		
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EF	Telfeyan, Roland, James Moyne, Nauman Chaudhry, James Pugmire, Scott Shellman, Duane Boning, William Moyne, Arnon Hurwitz, and John Taylor. October 1995. "A Multi-Level Approach to the Control of a Chemical-Mechanical Planarization Process." Minneapolis, Minnesota: 42 nd National Symposium of the American Vacuum Society.		
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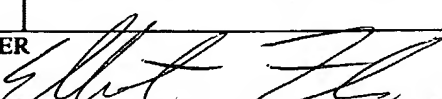
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EF	Chang, E., B. Stine, T. Maung, R. Divecha, D. Boning, J. Chung, K. Chang, G. Ray, D. Bradbury, O. S. Nakagawa, S. Oh, and D. Bartelink. December 1995. "Using a Statistical Metrology Framework to Identify Systematic and Random Sources of Die- and Wafer-level ILD Thickness Variation in CMP Processes." Washington, D.C.: International Electron Devices Meeting.		
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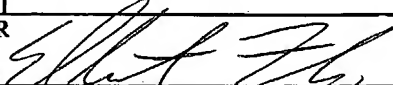
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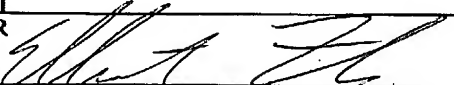
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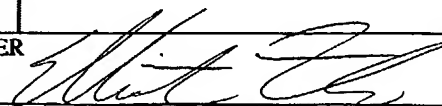
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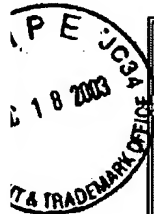
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October 17, 2003

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Sasson R. SOMEKH et al.

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October 17, 2003

GROUP

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
ELF	5,901,313	05/04/99	Wolf et al.			09/02/97
	6,002,989	12/14/99	Shiba et al.			04/01/97
	6,094,688	07/25/00	Mellen-Garnett et al.			03/12/98
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FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
ELF	WO 99/59200	11/18/99	WIPO			X	
ELF	WO 01/52319	07/19/01	WIPO			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

ELF	Williams, Randy, Dadi Gudmundsson, Kevin Monahan, Raman Nurani, Meryl Stoller and J. George Shanthikumar. October 1999. "Optimized Sample Planning for Wafer Defect Inspection," <i>Semiconductor Manufacturing Conference Proceedings, 1999 IEEE International Symposium on Santa Clara, CA</i> . Piscataway, NJ. pp. 43 - 46.
	23 July 2003. Invitation to Pay Additional Fees and Communication Relating to the Results of the Partial International Search for PCT/US02/19116.
	01 August 2003. Written Opinion for PCT/US01/27406.
ELF	20 August 2003. Written Opinion for PCT/US01/22833.
EXAMINER	DATE CONSIDERED
<i>Whit E. H.</i>	6/17/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.